ABSTRACT

METHODS AND APPARATUS FOR AN INDUCTION COIL ARRANGEMENT IN A PLASMA PROCESSING SYSTEM

An antenna arrangement in a plasma processing system for providing plasma uniformity across a substrate during substrate processing is provided. The arrangement includes a plurality of circular antenna assemblies. Each circular antenna assembly of the plurality of circular antenna assemblies includes a set of non-circular coils. Each non-circular coil of the set of non-circular coils is offset at a predetermined angle in an azimuthal direction. The arrangement also includes a set of power generators for powering the plurality of circular antenna assemblies.

FIG. 1